

**ABSTRACT OF THE DISCLOSURE**

A method of fabricating a liquid crystal display using a negative photo-resist.

A passivation layer covering a thin film transistor, a data line, and a gate line is formed on a transparent substrate. The passivation layer is patterned to define a contact hole that exposes a

5 drain electrode. A transparent conductive film in electrical contact with the drain electrode via the contact hole is then formed on the passivation layer. A negative-type photoresist is coated on the transparent conductive film. The transparent conductive film is then exposed with an image of the desired pixel electrode. The negative-type photoresist is then developed to expose portions of the transparent conductive film over a data line, a gate line, and the area  
10 of the thin film transistor area. The exposed transparent conductive film is then etched.

11  
12  
13  
14  
15  
16  
17  
18  
19  
20  
21  
22  
23  
24  
25  
26  
27  
28  
29  
30